

ABSTRACT OF THE INVENTION

5 An alignment system for a lithographic apparatus has a source of
alignment radiation; a detection system that has a first detector channel and a
second detector channel; and a position determining unit in communication
with the detection system. The position determining unit is constructed to
process information from said first and second detector channels in a
10 combination to determine a position of an alignment mark on a work piece, the
combination taking into account a manufacturing process of the work piece.
A lithographic apparatus has the above mentioned alignment system. Methods
of alignment and manufacturing devices with a lithographic apparatus use the
above alignment system and lithographic apparatus, respectively.

15